

ABSTRACT

The present invention provides a cleaning apparatus, a cleaning system and a cleaning method for a member used in the semiconductor field, excellent in cleaning capability and good in operation efficiency. The present invention is directed to a cleaning apparatus for cleaning the member used in the semiconductor field, which comprises: one nozzle or plural nozzles; and a jet mechanism for jetting a mist-like cleaning liquid (L1) with a high pressure from the one nozzle or the plural nozzles (52a) to the member (T) to be cleaned. The present invention is also directed to a cleaning system (30) for cleaning members used in the semiconductor field, which comprises: a loader section (40) for setting a member to be cleaned; an unloader section (70) for collecting the members; and a transport stage (80) for continuously transporting the member from the loader section to the unloader section, wherein a cleaning section (50) for cleaning the member with a mist-like cleaning liquid is provided on the transport stage, and the member is transported by the transport stage and is also cleaned in the cleaning section.